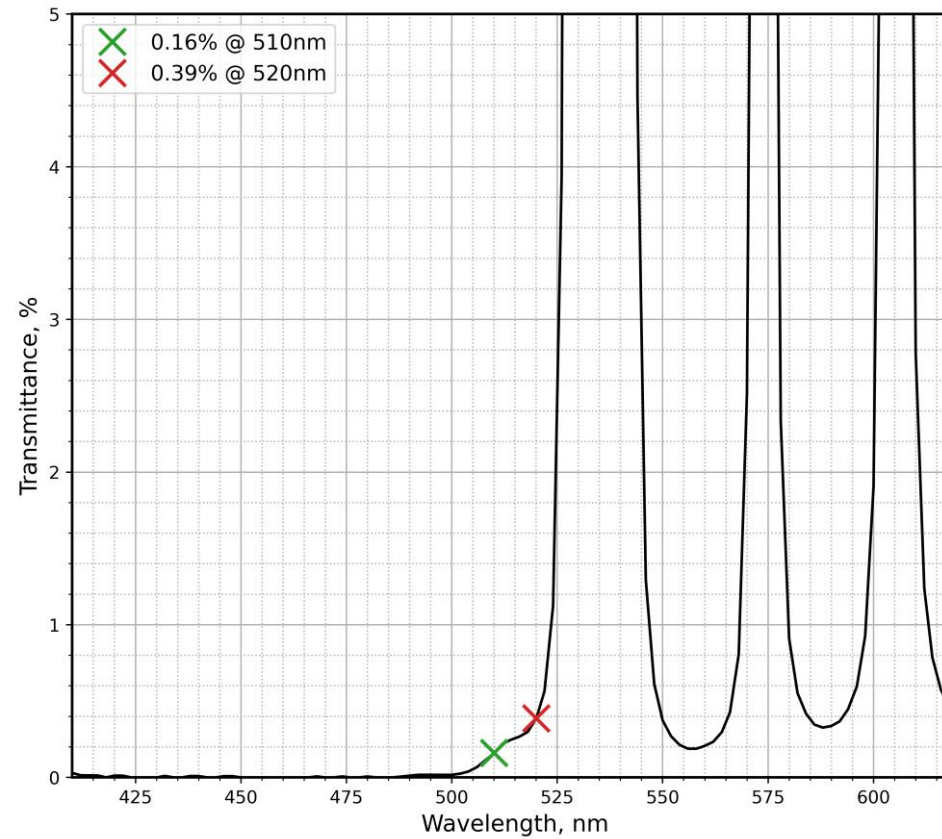


S1: Pol@510-520 nm ( $R_s > 99.0\%$ ,  $T_p > 95\%$ ),  $GDD_{\text{Ts}} < \pm 200 \text{ fs}^2$ , AOI = 45  
 S2: uncoated ( $R_p < 0.65\%$  of uncoated substrate)



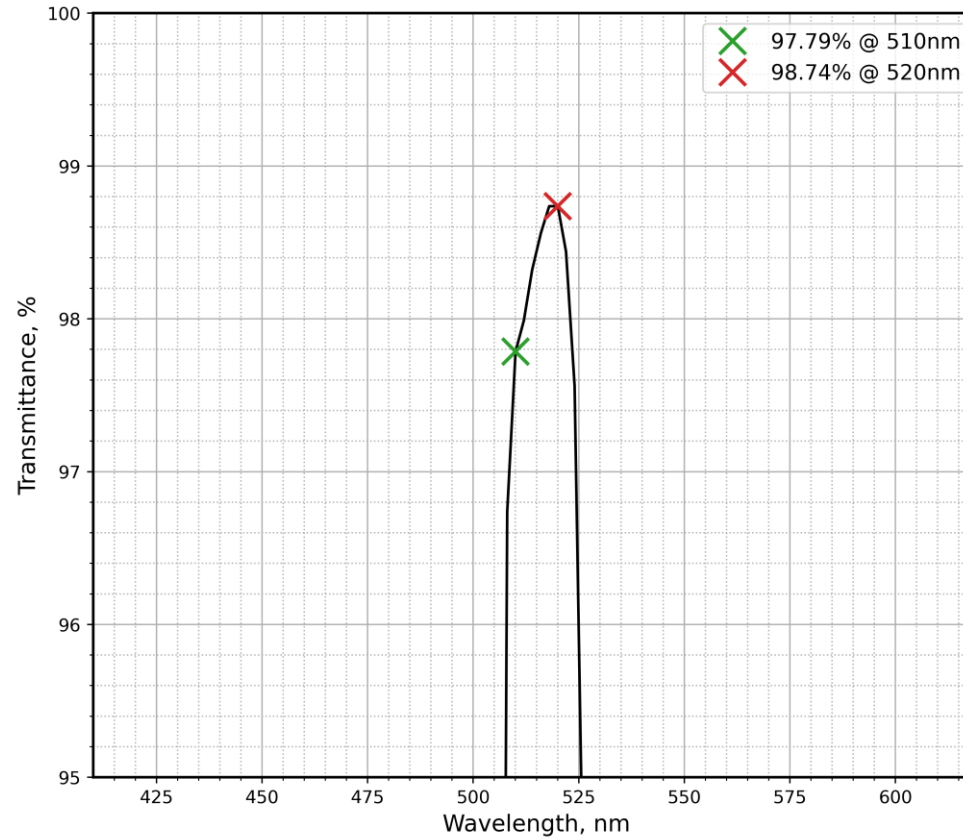
PO5391 Ts i45

Fig. 1.

SIDE MEASURED: S1 (good component)

COMMENTS:

S1: Pol@510-520 nm ( $R_s > 99.0\%$ ,  $T_p > 95\%$ ), GDD\_Rs < +/- 200 fs<sup>2</sup>, AOI = 45  
 S2: uncoated ( $R_p < 0.65\%$  of uncoated substrate)



PO5391 Tp i45

Fig. 2.

SIDE MEASURED: S1 (good component)

COMMENTS: